



US00D794753S

(12) **United States Design Patent**  
**Miller**(10) **Patent No.:** US D794,753 S  
(45) **Date of Patent:** \*\* Aug. 15, 2017(54) **SHOWERHEAD FOR A SEMICONDUCTOR PROCESSING CHAMBER**(71) Applicant: **Applied Materials, Inc.**, Santa Clara, CA (US)(72) Inventor: **Aaron Miller**, Sunnyvale, CA (US)(73) Assignee: **APPLIED MATERIALS, INC.**, Santa Clara, CA (US)(\*\*) Term: **15 Years**(21) Appl. No.: **29/560,672**(22) Filed: **Apr. 8, 2016**(51) LOC (10) Cl. .... **23-01**

(52) U.S. Cl.

USPC ..... **D23/213**(58) **Field of Classification Search**USPC ..... D23/213, 223, 226, 229, 230  
CPC ..... C23C 16/45565; B05B 1/00; B05B 1/18;  
B05B 9/01

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a showerhead for a semiconductor processing chamber, as shown and described.

**DESCRIPTION**

FIG. 1 is an isometric top view of a showerhead for a semiconductor processing chamber showing my new design.

FIG. 2 is an isometric bottom view thereof.

FIG. 3 is a top plan view thereof.

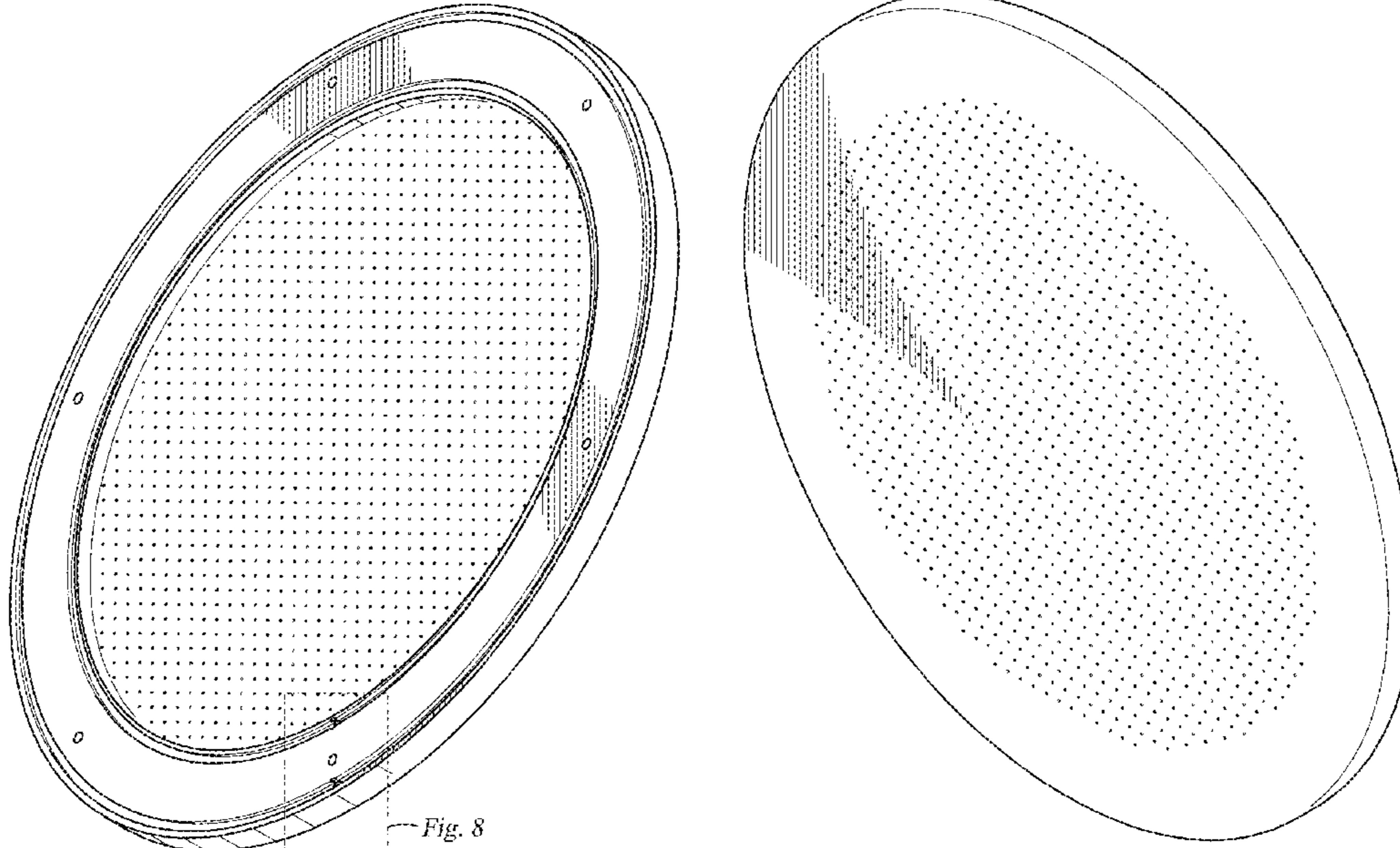
FIG. 4 is a bottom plan view thereof.

FIG. 5 is a side elevational view thereof, the other side elevational views being identical.

FIG. 6 is a cross-sectional view thereof taken along lines 6-6 of FIG. 3.

FIG. 7 is an enlarged view of a portion of FIG. 6; and,

FIG. 8 is an enlarged view of a portion of FIG. 1.

**1 Claim, 7 Drawing Sheets**

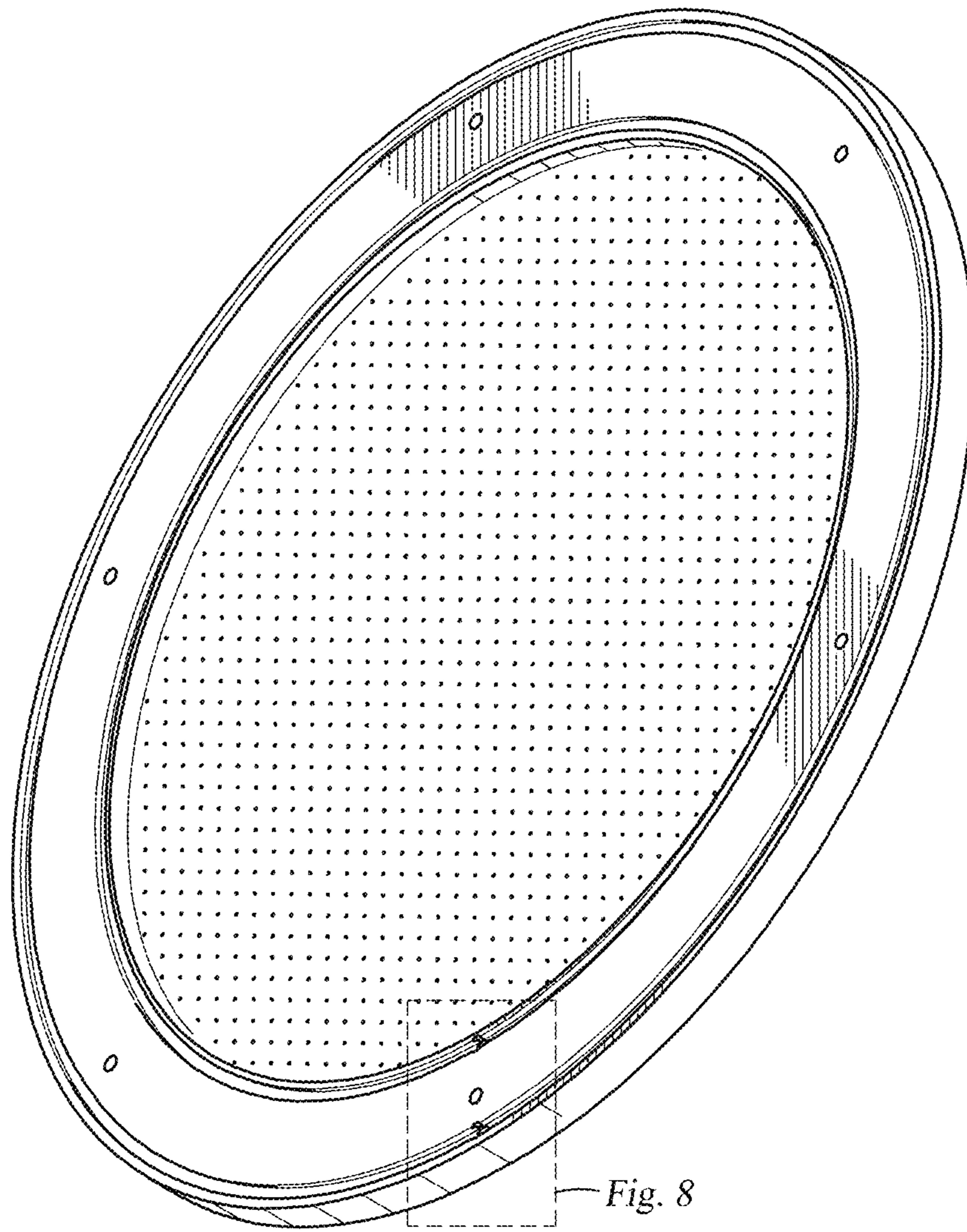
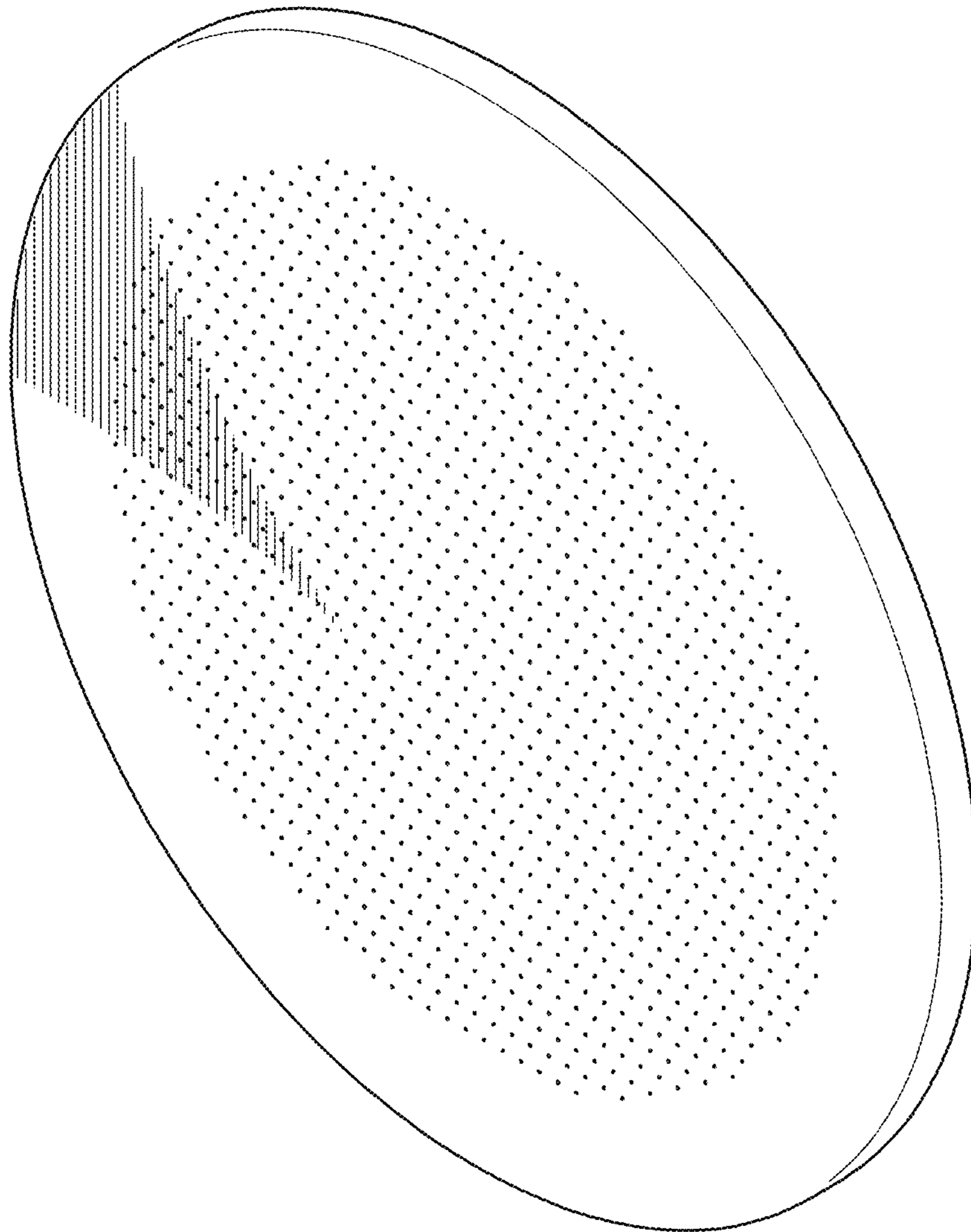
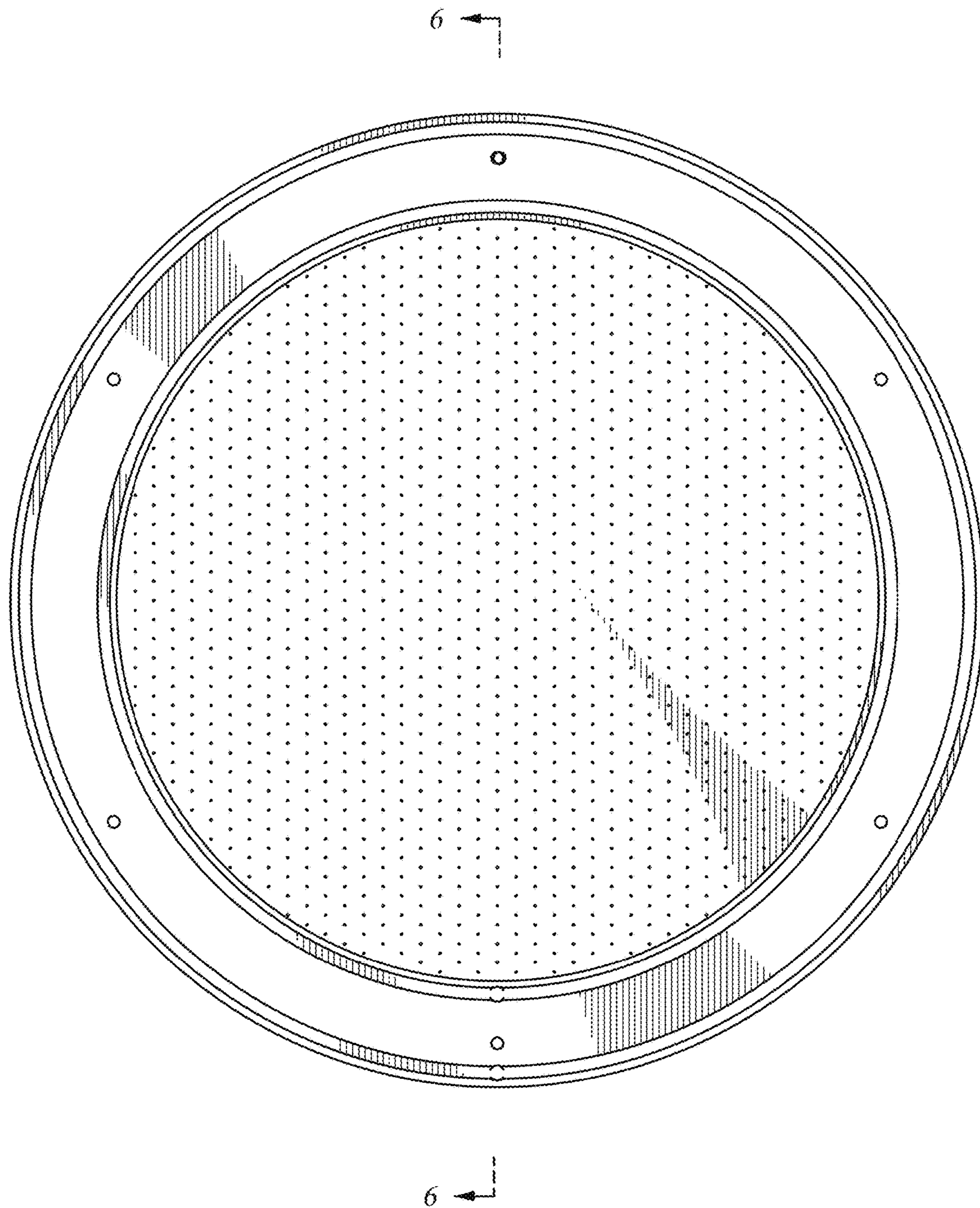


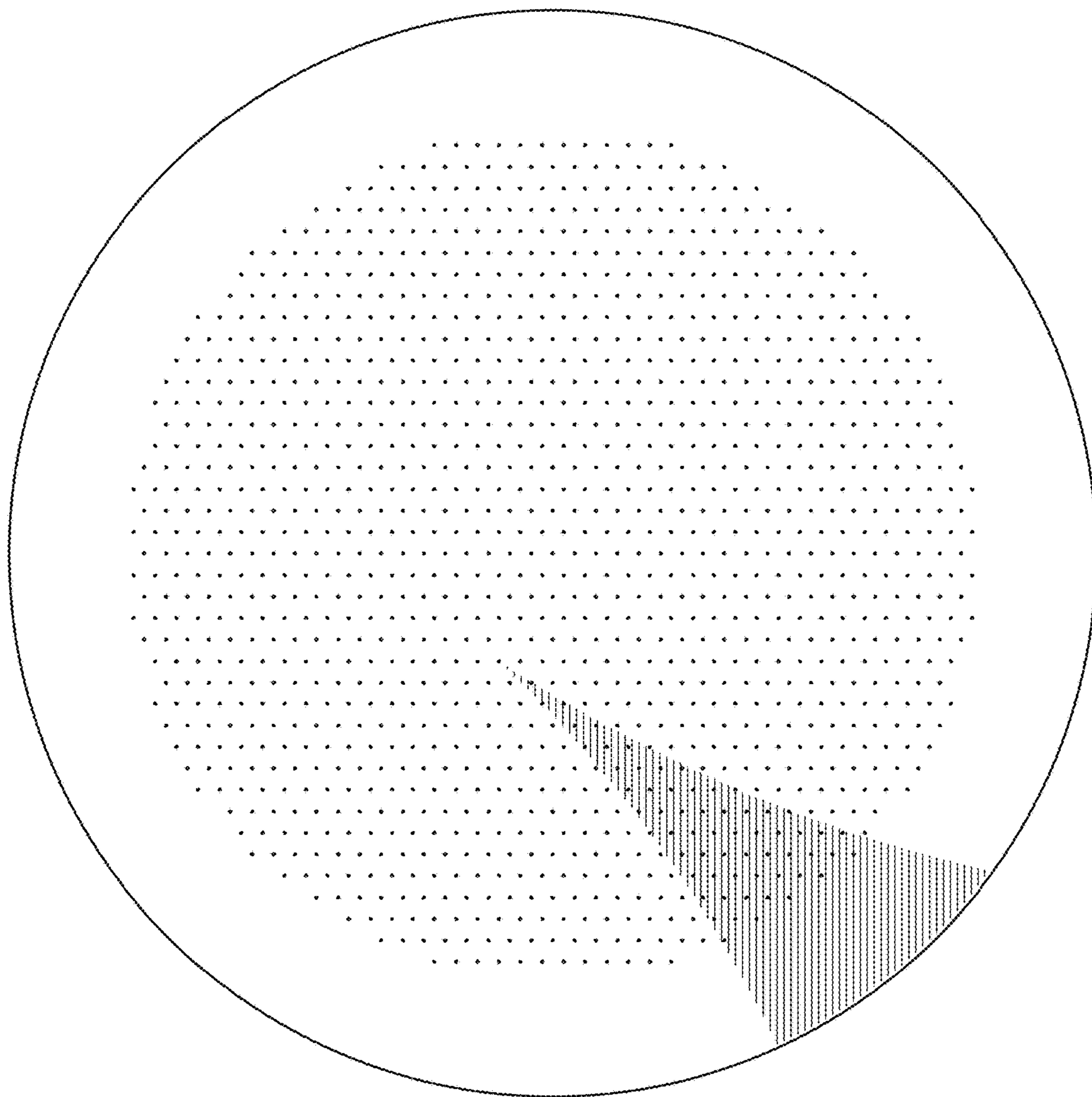
Fig. 1



*Fig. 2*



*Fig. 3*



*Fig. 4*



Fig. 5

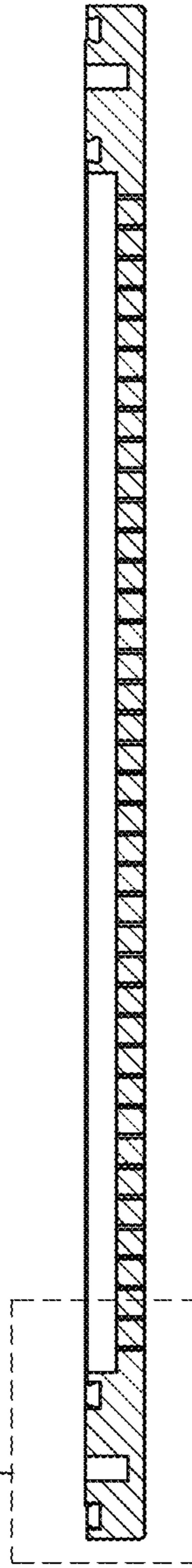
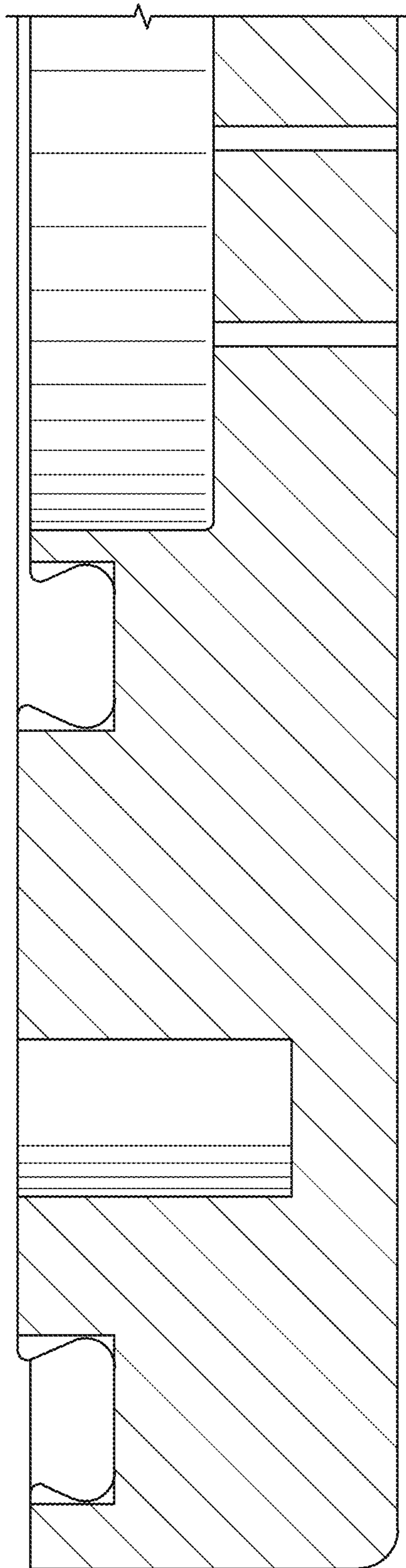


Fig. 6

Fig. 7



*Fig. 7*

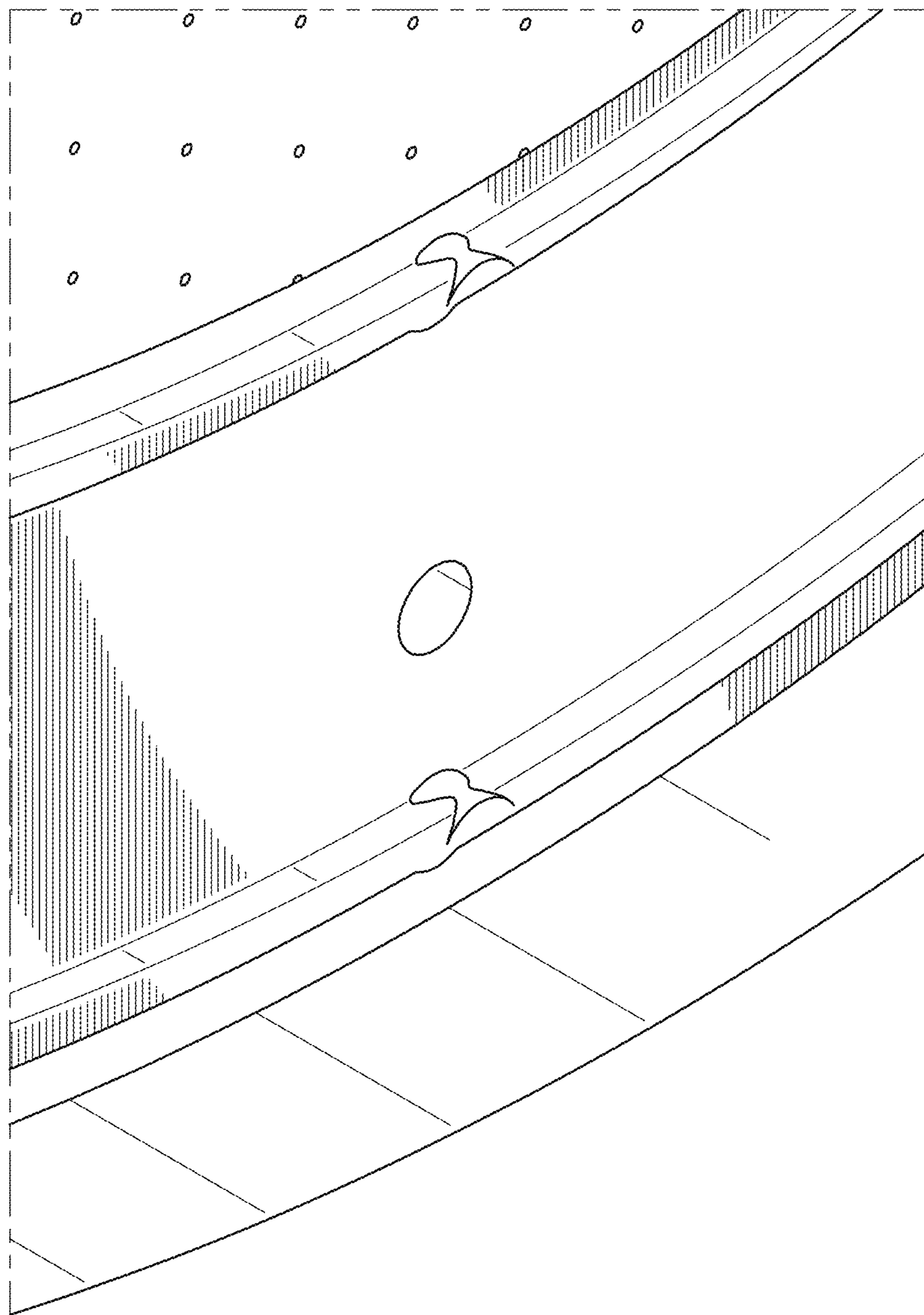


Fig. 8